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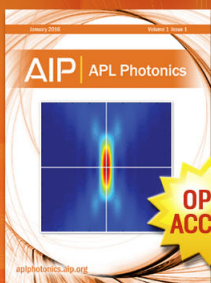
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## Dependence of inverse-spin Hall effect and spin-rectified voltage on tantalum thickness in Ta/CoFeB bilayer structure

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Ta-layer thickness ( $t_{\text{Ta}}$ ) dependence of the measured DC voltage  $V$  from the inverse-spin Hall effect (ISHE) in Ta/CoFeB bilayer structure is experimentally investigated using the ferromagnetic resonance in the TE<sub>011</sub> resonant cavity. The ISHE signals excluding the spin-rectified effect (SRE) were separated from the fitted curve of  $V$  against  $t_{\text{Ta}}$ . For  $t_{\text{Ta}} \approx \lambda_{\text{Ta}}$  (Ta-spin diffusion length = 2.7 nm), the deviation in ISHE voltage  $V_{\text{ISH}}$  between the experimental and theoretical values is significantly increased because of the large SRE contribution, which also results in a large deviation in the spin Hall angle  $\theta_{\text{SH}}$  (from 10% to 40%). However, when  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$ , the  $V_{\text{ISH}}$  values are consistent with theoretical values because the SRE terms become negligible, which subsequently improves the accuracy of the obtained  $\theta_{\text{SH}}$  within 4% deviation. The results will provide an outline for an accurate estimation of the  $\theta_{\text{SH}}$  for materials with small  $\lambda$  value, which would be useful for utilizing the spin Hall effect in a 3-terminal spintronic devices in which magnetization can be controlled by in-plane current. © 2015 AIP Publishing LLC.  
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Pure spin current  $J_s$ , a flow of electron spins without charge current in a solid material, is of great importance in a research field of spintronics.<sup>1</sup> The generation of the  $J_s$  are mostly done by using a ferromagnet (FM) from which spin-polarized electrons are injected into an adjacent non-magnetic material (NM). There are various injection mechanisms proposed such as thermal spin injection,<sup>2</sup> direct electric spin injection,<sup>3</sup> and spin-pumping effect driven by ferromagnetic resonance (FMR).<sup>4,5</sup> Among them, the FMR spin-pumping is widely used to determine spin Hall angle  $\theta_{\text{SH}}$  of the NM layer<sup>6-8</sup> because of better efficiency than others. Moreover, the spin injection by FMR spin pumping is free from the impedance mismatch problem.<sup>9</sup> The injected  $J_s$  in NM materials is converted into a charge current  $J_c$  via the inverse-spin Hall effect (ISHE) as<sup>4</sup>

$$J_c = \theta_{\text{SH}} \left( \frac{2e}{\hbar} \right) J_s \times \sigma, \quad (1)$$

where  $\theta_{\text{SH}}$ ,  $e$ ,  $\hbar$ , and  $\sigma$  denote the spin Hall angle (the efficiency of spin-charge conversion), the elementary charge, the Dirac constant, and the spin-polarization vector of the  $J_s$ , respectively. Note that the  $\theta_{\text{SH}}$ , which is related to spin-orbit interaction of the NM material, can be extracted from the measured ISHE voltage,  $V_{\text{ISH}}$  generated by the  $J_c$ . For example, the magnitude of the  $\theta_{\text{SH}}$  is reported in the high-resistivity materials of  $\beta$ -Ta (-0.15)<sup>10</sup> and  $\beta$ -W (-0.3).<sup>11</sup> Note that a large and reliable  $\theta_{\text{SH}}$  is very useful for optimizing the write impedance and minimizing the writing energy of a 3-terminal spin Hall effect device for achieving better performance and reliability in spin torque magnetic memory and spin logic applications, in comparison to conventional spin torque devices.<sup>10</sup>

The correct determination of the  $\theta_{\text{SH}}$  is essential in order to employ the spin Hall effect in the spintronic devices. However, unfortunately, the measured DC voltage  $V$  from FMR spin-pumping experiment contains not only the  $V_{\text{ISH}}$  induced by pure spin pumping but also spin-rectified voltage  $V_{\text{SR}}$ . The latter results from the non-zero electric field from microwave ( $E_{\text{MW}}$ ) which induced anisotropic magnetoresistance (AMR) and/or anomalous Hall effect (AHE) in the FM layer.<sup>4,8,12-14</sup> The non-negligible contribution of the  $V_{\text{SR}}$  (AMR voltage  $V_{\text{AMR}}$  and/or AHE voltage  $V_{\text{AH}}$ ) hinders the correct estimation of the  $\theta_{\text{SH}}$ , which may be the reason of the different reported  $\theta_{\text{SH}}$  of nominally identical materials.<sup>15,16</sup> There are numerous studies<sup>4,13,17,18</sup> performed for decreasing the spin-rectified effect (SRE) to attain a more accurate  $\theta_{\text{SH}}$  value. One of the examples is to place the samples at the center of a resonant cavity where the microwave magnetic field is maximized while the  $E_{\text{MW}}$  is minimized, which results in the suppression of the SRE contributions.<sup>17</sup> The other one is a selection of a proper microwave modes<sup>18</sup> in addition to the centering. A good understanding of these results is required for clarifying the origin of and correlation between ISHE and SRE in the bilayer structure.

In this study, the ISHE and the SRE in Ta ( $t_{\text{Ta}}$ )/CoFeB (10 nm) bilayers were investigated as a function of the Ta-layer thickness ( $t_{\text{Ta}}$ ) using FMR spin-pumping in the TE<sub>011</sub> resonant cavity. When  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$  (Ta-spin diffusion length = 2.7 nm),<sup>16</sup> the  $V_{\text{ISH}}$  values are consistent with theoretical values because the  $V_{\text{SR}}$  is negligible. Furthermore, the accuracy of  $\theta_{\text{SH}}$  can be improved to within 4% deviation due to the reduced SRE. This indicates that the NM layer thickness for the FMR spin-pumping experiment to obtain the  $\theta_{\text{SH}}$  should be appropriately chosen in the case of the NMs of small spin diffusion length  $\lambda$ , such as Ta.

Figure 1(a) shows schematic illustrations of the measurements of the FMR in the CoFeB single layer and of the

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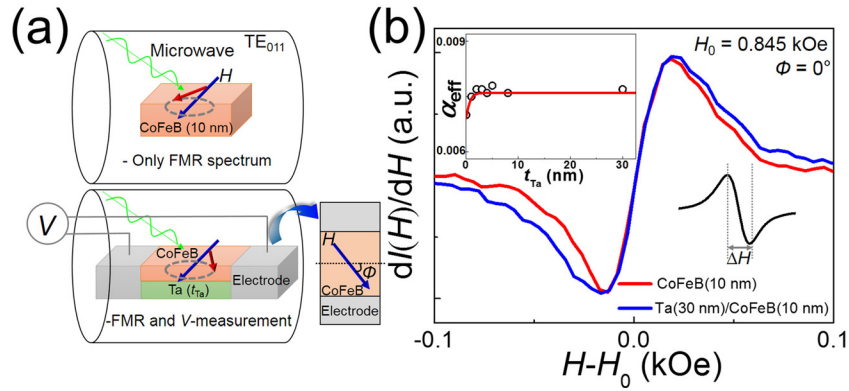


FIG. 1. (a) Schematic illustrations of the measurements of the samples (CoFeB single layer and Ta/CoFeB bilayer) in the TE<sub>011</sub> resonant cavity. Here, the samples are placed near the center of the resonant cavity to minimize the spin-rectified effect (SRE). The external magnetic field  $H$  is applied along the sample plane.  $\phi$  is the in-plane angle between  $H$  and transverse axis. (b) The  $H$  dependence of the ferromagnetic resonance for the CoFeB (10 nm) single layer and Ta (30 nm)/CoFeB (10 nm) bilayer. Here,  $I$ ,  $\Delta H$ , and  $H_0$  ( $=0.845$  kOe) denote the microwave absorption intensity, the spectral width, and the resonance magnetic field, respectively. The inset shows the  $t_{\text{Ta}}$  dependence of  $\alpha_{\text{eff}}$  (the effective Gilbert damping constant) estimated from the ferromagnetic resonance results obtained for the CoFeB single layer and Ta/CoFeB bilayer samples.

FMR and  $V$  in the Ta/CoFeB bilayer. The bilayer samples of a 10-nm-thick FM CoFeB layer and a Ta layer of thickness  $t_{\text{Ta}}=1\text{--}30$  nm were sputtered on thermally oxidized Si substrates. The dimension of the samples is 1 mm (width)  $\times$  2 mm (length). In order to measure  $V$ , two electrodes are kept in contact with both ends of the bilayer sample (the sign of  $V$  is determined by the measurement conditions and is considered to be positive for the present measurements). In accordance with the previous studies,<sup>18</sup> the present experiments minimize the effect of  $E_{\text{MW}}$  by optimizing the DUT (device under test) centering; the DUT is placed near the center of a TE<sub>011</sub> cylindrical cavity.

Note that the typical spin-pumping method with a coplanar wave-guide (CPW) shows a superimposed signal of  $V_{\text{ISH}}$  and  $V_{\text{SR}}$ ,<sup>8</sup> because of non-zero angle ( $\phi$ ) between applied field ( $H$ ) and longitudinal axis of the sample, with a relation of the ISHE ( $\propto \sin(\phi)$ ) and AMR ( $\propto \sin(\phi)\cos(\phi)$ ). On the other hand, the cavity method has provided more convenient way to separate AMR ( $V_{\text{AMR}}\sin(2\phi)\sin(\phi)$ ) and ISHE ( $V_{\text{ISH}}\cos(\phi)$ ) signal, since the  $\phi$  can be zero.<sup>13</sup> Here, the  $\phi$  ( $=90^\circ - \phi$ ) is the in-plane angle between  $H$  and transverse axis. Therefore, the cavity method has an angle ( $\phi$ ) depending AMR free environment when  $\phi$  is zero, and finally, the  $V_{\text{ISH}}$  shows a clear dependence of the  $t_{\text{Ta}}$ .

Figure 1(b) shows the measured FMR as a function of  $H$  for the CoFeB single layer and the Ta (30 nm)/CoFeB (10 nm) bilayer. Here, the microwave frequency is 9.46 GHz, microwave power is 50 mW, and resonance field  $H_0$  is 0.845 kOe. In the FMR data,  $I$  denotes the microwave absorption intensity. The full width at half maximum of  $I(H)$ ,  $\Delta H$  ( $=4\pi f_0 \alpha_{\text{eff}} / \sqrt{3}\gamma$ ), shown in the inset, for the CoFeB is enlarged by attaching the Ta layer, where  $f_0$ ,  $\alpha_{\text{eff}}$ , and  $\gamma$  are the resonance frequency, effective Gilbert damping constant, and gyromagnetic ratio, respectively. The  $\alpha_{\text{eff}}$  is determined by modification of the intrinsic damping constant,  $\alpha_0$ , of CoFeB by additional damping ( $\Delta\alpha$ ) from the spin pumping effect. The increase in the damping constant demonstrates an evidence of the  $J_s$  injection using FMR spin-pumping. The inset shows the  $t_{\text{Ta}}$  dependence of the  $\alpha_{\text{eff}}$  (symbols) extracted from  $\Delta H$ . Here, the  $\alpha_{\text{eff}}$  for the Ta/CoFeB bilayer is given by<sup>19</sup>

$$\alpha_{\text{eff}}(t_{\text{Ta}}) \approx \alpha_0 + \frac{A_1}{1 + \left(2\sqrt{(Z_{\text{Ta}}\alpha_{\text{fs}})^4/3 \tanh(t_{\text{Ta}}/\lambda_{\text{Ta}})}\right)^{-1}}, \quad (2)$$

where  $Z_{\text{Ta}}$  and  $\alpha_{\text{fs}}$  are the atomic number of Ta and fine-structure constant, respectively. The parameter  $A_1$  ( $=g\mu_{\text{B}}g^{\uparrow\downarrow}/4\pi M_s t_{\text{CoFeB}}$ ) is a constant for Ta/CoFeB structures which involves the  $g$ -factor, the Bohr magneton  $\mu_{\text{B}}$ , the saturation magnetization  $M_s$ , thickness of CoFeB layer  $t_{\text{CoFeB}}$ , and the spin mixing conductance  $g^{\uparrow\downarrow}$ . The red curve shows a fitting to Eq. (2) with  $\lambda_{\text{Ta}}=2.7$  nm,  $A_1=0.002$ , and  $\alpha_0=0.007$  ( $y$ -intercept). The value of  $\alpha_0$  for the CoFeB single layer agrees reasonably with previous experimental results.<sup>18</sup> The reported  $\alpha_0=0.015$  for a 5-nm CoFeB single layer is twice that a 10 nm CoFeB, thus  $\alpha_0 \propto t_{\text{CoFeB}}^{-1}$ .<sup>20,21</sup>  $\alpha_{\text{eff}}$  is initially increased with  $t_{\text{Ta}}$  up to the  $\lambda_{\text{Ta}}$  and no variation at larger  $t_{\text{Ta}}$ . This indicates that the  $J_s$  value at the Ta/CoFeB interface is suppressed at smaller  $t_{\text{Ta}}$  due to the backflow of the  $J_s$ , which can be neglected for larger  $t_{\text{Ta}}$  than the  $\lambda_{\text{Ta}}$ . These results are also consistent with the previous experimental data for  $\alpha_{\text{eff}}$  with respect to the thickness of the NM layer.<sup>19</sup>

Figures 2(a) and 2(b) show the  $H$  dependence of  $V$  measured for the Ta ( $t_{\text{Ta}}$ )/CoFeB (10 nm) bilayer samples under the FMR condition. In the  $t_{\text{Ta}} < \lambda_{\text{Ta}}$  region (shown in Figure 2(a)), the amplitude of  $V(H)$  is increased with  $t_{\text{Ta}}$ . Furthermore, the antisymmetric component is clearly observed in the  $V(H)$  curve, which can be attributed to the undesired SRE signal. In other words, the  $V(H)$  is given by the sum of the two contributions: ISHE and SRE, which have different symmetry with respect to the resonance magnetic field. The voltage from the ISHE typically shows a symmetric curve that can be expressed by a Lorentzian curve, while that from the SRE does an antisymmetric dispersive curve. On the other hand, in the  $t_{\text{Ta}} > \lambda_{\text{Ta}}$  region (shown in Figure 2(b)), the amplitude of  $V(H)$  shows a monotonic decrease with the increase in  $t_{\text{Ta}}$  and the shape of  $V(H)$  curves become more symmetric. Next, in order to extract the ISHE and SRE components from the experimental  $V(H)$  curves, the  $V(H)$  data were analyzed by fitting into a simple function consisted of the  $V_{\text{ISH}}$  and the  $V_{\text{SR}}$ .

Figure 3(a) shows the theoretical fits of the experimental  $V(H)$  data (Figure 2) obtained from the Ta ( $t_{\text{Ta}}$ )/CoFeB (10 nm) bilayer with  $t_{\text{Ta}}$  varying from 1 nm to 30 nm. The measured  $V(H)$  signals under the FMR condition are well-fitted using the following function<sup>18</sup>

$$V(H) = V_{\text{ISHE}}(H) + V_{\text{SRE}}(H) \\ = V_{\text{ISH}} \frac{\Delta H^2}{(H - H_0)^2 + \Delta H^2} + V_{\text{SR}} \frac{-2\Delta H(H - H_0)}{(H - H_0)^2 + \Delta H^2}, \quad (3)$$

where the first and second terms indicate the ISHE and SRE contributions, respectively. The terms of  $V_{\text{ISHE}}(H)$  and the

$V_{\text{SRE}}(H)$  are proportional to the inverse-spin Hall coefficient of Ta and the spin rectification coefficient of CoFeB, respectively. It is worth noting that the shapes of the  $V(H)$  curves are dependent on  $t_{\text{Ta}}$ . The  $V(H)$  curve becomes symmetric on increasing  $t_{\text{Ta}}$ .

Figure 3(b) presents the  $t_{\text{Ta}}$  dependence of the  $V_{\text{ISH}}$  (magnitude of  $V_{\text{ISHE}}(H)$ ) and  $V_{\text{SR}}$  (magnitude of  $V_{\text{SRE}}(H)$ ) extracted from the fitted  $V(H)$  curves, which is shown in Figure 3(a).  $V_{\text{ISH}}$  (red open squares) is designated as the peak height of the Lorentzian function. As is well known,  $V_{\text{ISH}}$  for the bilayer system is theoretically given by<sup>19</sup>

$$V_{\text{ISH}}(t_{\text{Ta}}) \approx \frac{c_1 \theta_{\text{SH}} \tanh(t_{\text{Ta}}/2\lambda_{\text{Ta}}) \left( 1 + \left( 2\sqrt{(Z_{\text{Ta}}\alpha_{\text{fs}})^4/3} \tanh(t_{\text{Ta}}/\lambda_{\text{Ta}}) \right)^{-1} \right)^{-1}}{\left( 1 + (\rho_{\text{CoFeB}}/\rho_{\text{Ta}} t_{\text{CoFeB}}) t_{\text{Ta}} \right) \left( \alpha_0 + A_1 \left( 1 + \left( 2\sqrt{(Z_{\text{Ta}}\alpha_{\text{fs}})^4/3} \tanh(t_{\text{Ta}}/\lambda_{\text{Ta}}) \right)^{-1} \right)^{-1} \right)^2}, \quad (4)$$

where  $\rho_{\text{CoFeB}}$  is the resistivity of CoFeB and  $\rho_{\text{Ta}}$  is the resistivity of Ta. The parameter  $c_1$  involves physical constants such as the initial  $J_s$  value at the Ta/CoFeB interface  $J_s^0$ ,  $f_0$ ,  $\gamma$ ,  $M_s$ , and the microwave magnetic field  $h_{\text{rf}}$ . The magenta line in the Figure 3(b) is the best fit to the  $V_{\text{ISH}}$  data obtained with Eq. (4) and reasonable material parameters. The experimentally measured parameters are  $\alpha_0 \approx 0.007$ ,  $A_1 \approx 0.002$ ,  $\rho_{\text{Ta}} \approx 210 \mu\Omega\cdot\text{cm}$ , and  $\rho_{\text{CoFeB}} \approx 180 \mu\Omega\cdot\text{cm}$ , and the

well-fitting parameters are  $\lambda_{\text{Ta}} = 2.5 \pm 0.5$  nm (the deviation originates from the quality of the thin film) and  $c_1 = 0.03 \pm 0.01 \mu\text{V}$  (the calculated  $h_{\text{rf}} \approx 1$  Oe). The parameters are comparable to previous experimental data for  $V_{\text{ISH}}$  vs. the thickness of a Pt layer (with a fixed FM layer).<sup>19</sup> The  $V_{\text{ISH}}$  values show a monotonic decrease with the increase in  $t_{\text{Ta}}$  for  $t_{\text{Ta}} > \lambda_{\text{Ta}}$ . According to a simple circuit model, this originates from the reduction in the resistance of Ta,  $R_{\text{Ta}}$  ( $= \rho_{\text{Ta}} l/(wt_{\text{Ta}})$ , where  $l$  ( $w$ ) is a length (width) of the sample). This is because the measured voltage is described as  $1/V_{\text{ISH}} = 1/(R_{\text{Ta}} I_c) + 1/(R_{\text{CoFeB}} I_c)$ , where  $R_{\text{CoFeB}}$  and  $I_c$  are the resistance of the CoFeB layer and the induced current from spin pumping. On the contrary, in the  $t_{\text{Ta}} < \lambda_{\text{Ta}}$  region, the  $V_{\text{ISH}}$  values are decreased with decreasing  $t_{\text{Ta}}$  because  $J_s^0$  generated by the spin-pumping effect is decreased owing to the backflow of  $J_s$ , which is related to the variation of  $\alpha_{\text{eff}}$  (see the inset of Figure 1(b)). To analyze the contribution of SRE in the bilayer according to  $t_{\text{Ta}}$ , the NM/FM bilayer is assumed to be two independent resistors ( $R_{\text{CoFeB}}$  or  $R_{\text{Ta}}$ ) connected in parallel; this is called the two-channel model. In this model, it can be also assumed that the spin-rectified voltage is generated only by the CoFeB layer. The total induced current  $I_{\text{total}}$  and voltage  $V_{\text{total}}$  in the sample can be expressed as  $I_{\text{total}} = I_{\text{CoFeB}} + I_{\text{Ta}}$  and  $V_{\text{total}} = R_{\text{CoFeB}} I_{\text{CoFeB}} = R_{\text{Ta}} I_{\text{Ta}}$ , where the subscripts indicate the CoFeB and Ta layers, respectively. Therefore, the  $V_{\text{SR}}$  as a function of the  $t_{\text{Ta}}$  can be expressed as<sup>22</sup>

$$V_{\text{SR}}(t_{\text{Ta}}) \approx \frac{C_{\text{SRE}} (\propto \rho_{\text{SR}})}{(\rho_{\text{CoFeB}}/\rho_{\text{Ta}} t_{\text{CoFeB}}) t_{\text{Ta}} + 1}, \quad (5)$$

where  $\rho_{\text{SR}}$  is resistivity corresponded to the spin-rectification in the bilayer. The cyan line in Figure 3(b) is the best fit to the  $V_{\text{SR}}$  data obtained with Eq. (5),  $C_{\text{SRE}} \approx 22 \mu\text{V}$ , and the above-mentioned parameters ( $\rho_{\text{CoFeB}}$ ,  $\rho_{\text{Ta}}$ ,  $t_{\text{CoFeB}}$ ). The experimental  $V_{\text{SR}}$  values in the bilayer system are consistent

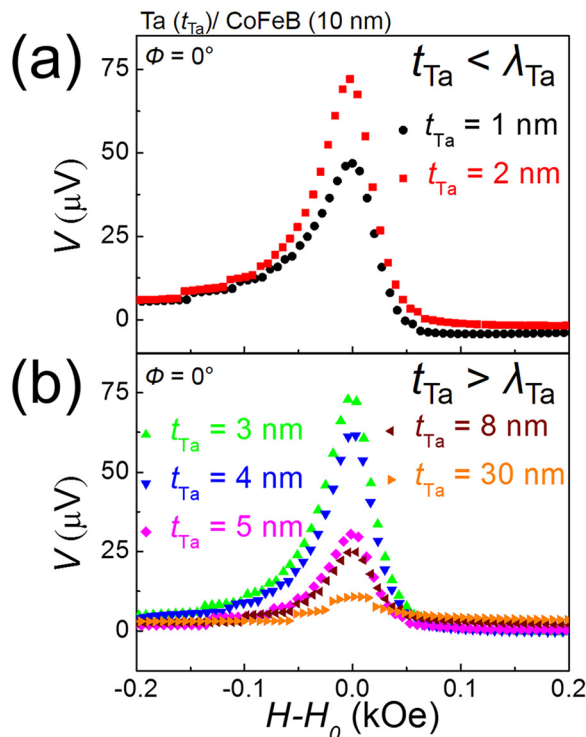


FIG. 2.  $H$  dependence of  $V$  for Ta ( $t_{\text{Ta}}$ )/CoFeB (10 nm) bilayer samples. The experimental curves of  $V$  are divided on the basis of the Ta-spin diffusion length  $\lambda_{\text{Ta}}$  ( $= 2.7$  nm) as (a)  $t_{\text{Ta}} < \lambda_{\text{Ta}}$  and (b)  $t_{\text{Ta}} > \lambda_{\text{Ta}}$ .

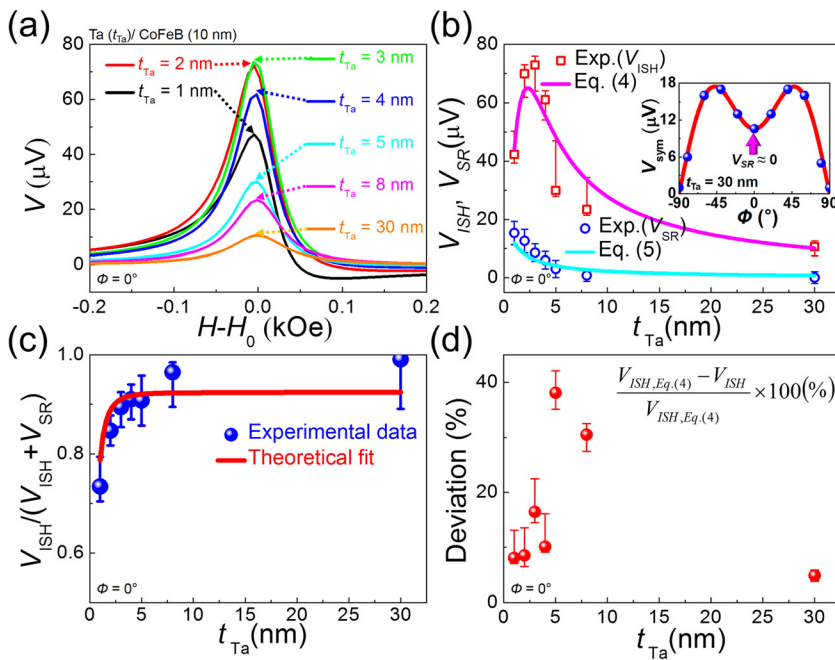


FIG. 3. (a) The fitting results from the experimental  $V(H)$  data (in Figure 2). (b) The  $t_{\text{Ta}}$  dependence of  $V_{\text{ISH}}$  (open squares) and  $V_{\text{SR}}$  (open circles). The data points are taken from Figure 3(a). The solid magenta line shows the fitting result for the  $V_{\text{ISH}}$  data. The solid cyan line shows the fitting result for the  $V_{\text{SR}}$  data. Inset shows the dependence of the  $V_{\text{sym}}$  as a function of  $\phi$ . (c) The  $t_{\text{Ta}}$  dependence of  $V_{\text{ISH}}/(V_{\text{ISH}} + V_{\text{SR}})$  ratios. The red curve shows the theoretical fit. (d) The  $t_{\text{Ta}}$  dependence of deviation (%) between the theoretical and the experimental  $V_{\text{ISH}}$  values is shown.

with the theoretical values (from Eq. (5)) based on the two-channel model. Note that the  $V_{\text{SR}}$  values are especially increased with decreasing  $t_{\text{Ta}}$ . The inset in Figure 3(b) shows data for the symmetric component of  $V(H, \phi)$  ( $= V_{\text{sym}}$ ) fitted by Eq. (3) for fixed  $t_{\text{Ta}} = 30$  nm and varying  $\phi$ . The solid line in the inset of Figure 3(b) is the well fit to the experimental data using  $V_{\text{sym}}(\phi) = V_{\text{ISH}} (= 10.6 \mu\text{V})\cos(\phi) + V_{\text{AMR}} (= 13.8 \mu\text{V})\sin(2\phi)\sin(\phi)$ , according to Ref. 13. From this result, the SRE contribution to the  $V(H, \phi)$  in the resonant cavity system is practically negligible at the  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$  and  $\phi = 0^\circ$ .

The relative magnitude of the ISHE expressed by  $V_{\text{ISH}}/(V_{\text{ISH}} + V_{\text{SR}})$ , as shown in Figure 3(c), is initially increased and saturated with an increase of the  $t_{\text{Ta}}$ , which is due to the reduction of SRE. The red curve shows  $V_{\text{ISH}}/(V_{\text{ISH}} + V_{\text{SR}})$  vs.  $t_{\text{Ta}}$  estimated from Eqs. (4) and (5). These results indicate that the SRE contribution is practically negligible for  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$ . With this reason, in the  $t_{\text{Ta}} < \lambda_{\text{Ta}}$  region where the SRE is relatively large, the deviation in  $V_{\text{ISH}}$  values between the theoretical (Eq. (4)), and experimental data are also increased by 10%–40% (Figure 3(d)); the deviation is defined by  $(V_{\text{ISH, Eq. (4)}} - V_{\text{ISH, experimental data}})/V_{\text{ISH, Eq. (4)}} \times 100$ . However, when  $t_{\text{Ta}}$  is sufficiently large where the SRE is negligible, the deviation in  $V_{\text{ISH}}$  can be decreased to within 4%.

Formerly, the measurement of  $V(H)$  is focused on sample geometry (length, width, and thickness dimensions), which is determined to obtain a highly suitable  $V_{\text{ISH}}$  value.<sup>19</sup> It was reported that the magnitude of  $V_{\text{ISH}}$  is proportional to the length of the bilayer sample and does not vary on the width of the bilayer sample.<sup>23</sup> Moreover, the  $V_{\text{ISH}}$  attains its maximum value when the thickness of the NM layer in the NM/FM bilayer is close to the  $\lambda$  of the NM material.<sup>19</sup> Unfortunately, for materials with a small  $\lambda$  such as Ta, the maximum  $V_{\text{ISH}}$  value (assuming  $t_{\text{Ta}} \approx \lambda_{\text{Ta}}$ ) showed a large deviation from the model calculation due to the large SRE contribution, regardless of the resistivity of each layer (CoFeB and Ta). Consequently, the  $\theta_{\text{SH}}$  obtained from the

$V_{\text{ISH}}$  also shows a discrepancy with a theoretical  $\theta_{\text{SH}}$  value for the Ta material calculated from Eq. (4) with the above-mentioned parameters  $\rho_{\text{Ta}}$ ,  $\rho_{\text{CoFeB}}$ ,  $c_1$ ,  $\alpha_0$ ,  $\lambda_{\text{Ta}}$ , and  $V_{\text{ISH}}$ . When  $t_{\text{Ta}} (= 3 \text{ nm}) \approx \lambda_{\text{Ta}}$ , the obtained  $\theta_{\text{SH}}$  value for Ta with an experimental value of  $V_{\text{ISH}} = 69 \pm 8 \mu\text{V}$  is  $0.025 \pm 0.008$  (the deviation originates from the SRE). However, when  $t_{\text{Ta}} (= 30 \text{ nm}) \gg \lambda_{\text{Ta}}$ , the  $\theta_{\text{SH}}$  value for Ta with  $V_{\text{ISH}} = 9.8 \pm 2.8 \mu\text{V}$  is  $0.02 \pm 0.0007$ . There have been several discrepancies in the values of  $\theta_{\text{SH}}$  reported in the literature,<sup>15</sup> which could be explained by the fact that the antisymmetric component of  $V_{\text{SR}}$  is not appropriately considered when measuring  $V_{\text{ISH}}$  in the bilayer structure.<sup>24</sup> It is important that the  $\theta_{\text{SH}}$  value for Ta can be obtained with high accuracy at  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$  by eliminating the SRE contribution in the  $V_{\text{ISH}}$  measurement.

In summary, the  $t_{\text{Ta}}$  dependences of the spin pumping voltage  $V(H, \phi)$  (from ISHE and SRE) in Ta ( $t_{\text{Ta}}$ )/CoFeB bilayers were experimentally investigated using the FMR in the TE<sub>011</sub> resonant cavity. The ISHE signals are well separated from the fitted curve of  $V(H, \phi)$  against  $t_{\text{Ta}}$ . For  $t_{\text{Ta}} \approx \lambda_{\text{Ta}}$ , the deviation in  $V_{\text{ISH}}$  values between the experimental and theoretical values are increased with decreasing  $t_{\text{Ta}}$  because of the large SRE contribution, which also increases the deviation in the  $\theta_{\text{SH}}$  value for Ta from 10% to 40% ( $0.025 \pm 0.008$ ). However, when  $t_{\text{Ta}} \gg \lambda_{\text{Ta}}$ , the  $V_{\text{ISH}}$  values are consistent with theoretical values because of the negligible SRE (with increasing  $t_{\text{Ta}}$ ). Furthermore, the accuracy of  $\theta_{\text{SH}}$  is improved with reduced SRE to  $\theta_{\text{SH}} = 0.02 \pm 0.0007$  (within 4% deviation). These results will provide an outline for accurately estimating the  $\theta_{\text{SH}}$  parameter for materials with a large  $\theta_{\text{SH}}$  value and a small  $\lambda$  value.

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